

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-2347		Priority SERIAL NO. 10000456 <i>10/626952</i>	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Ying Huang et al.		FILING DATE <i>8/23/03</i>	
				GROUP <i>2815</i>			

  

U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate	
<i>JN</i>	AA	5,946,601	8/99	Wong et al.			
	AB	6,033,979	3/00	Endo			
	AC	6,037,664	3/00	Zhao et al.			
	AD	6,046,104	4/00	Kepler			
	AE	6,057,417	5/00	Arnold et al.			
	AF	6,284,657 B1	09/01	Chooi et al.			
	AG	5,122,483	06/92	Sakai et al.			
	AH	6,265,779 B1	07/01	Grill et al.			
	AI	6,410,437 B1	06/25/02	Flanner et al.			
	AJ						
	AK						
	AL						

  

FOREIGN PATENT DOCUMENTS							
Document Number	Date	Country	Class	Subclass	Translation		
					Yes	No	
AM							
AN							
AO							
AP							
AQ							

  

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)		
AR		Beliga, John, "Options for CVD of Dielectrics Include Low-k Materials," Semiconductor International June 1998, pp. 1-6
<i>JN</i>	AS	Singer, Peter, "Dual-Damascene Challenges Dielectric-Etch," Semiconductor International August 1999, pp. 1-5
	AT	

  

EXAMINER <i>JOSEPA NGUYEN</i>	DATE CONSIDERED <i>9/21/04</i>
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



PTO-1479		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-2347		Priority SERIAL NO. 40039-446-10/655952	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Ying Huang et al.		FILING DATE 9/23/03	
				GROUP 2815			
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
JN	AA	5,946,601	8/99	Wong et al.			
	AB	6,033,979	3/00	Endo			
	AC	6,037,664	3/00	Zhao et al.			
	AD	6,046,104	4/00	Kepler			
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	AF	6,284,657 B1	09/01	Chooi et al.			
	AG	5,122,483	06/92	Sakai et al.			
	AH	6,265,779 B1	07/01	Grill et al.			
	AJ	6,410,437 B1	06/25/02	Flanner et al.			
	AJ						
	AK						
	AL						
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation Yes No
	AM						
	AN						
	AO						
	AP						
	AQ						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
ON	AR			Ballga, John, "Options for CVD of Dielectrics Include Low-k Materials," Semiconductor International June 1998, pp. 1-4			
	AS			Singer, Peter, "Dual-Damascene Challenges Dielectric-Etch," Semiconductor International August 1999, pp. 1-3			
	AT						
EXAMINER JOSEPH NGUYEN				DATE CONSIDERED 9/21/04			
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